

Form PTO-1449 (modified)

Atty. Docket No.
2000.070500/SFDSerial No.
09/897,624

List of Patents and Publications for Applicant's
INFORMATION DISCLOSURE STATEMENT
 (Use several sheets if necessary)

Applicants
Marilyn I. WrightFiling Date:
July 2, 2001Group:
2812 2823U.S. Patent Documents
See Page 1

Foreign Patent Documents

Other Art
See Page 1-2**U.S. Patent Documents**

| Exam. Init. | Ref. Des. | Document Number | Date | Name | Class | Sub Class | Filing Date of App. |
|-------------|-----------|-----------------|-----------|----------------|-------|-----------|---------------------|
| 8F | A1 | 5,880,838 | 3/9/1999 | Marx, et al. | 356 | 351 | 6/5/1996 |
| 8F | A2 | 5,867,276 | 2/2/1999 | McNeil, et al. | 356 | 445 | 3/7/1997 |
| 8F | A3 | 5,393,624 | 2/28/1995 | Ushijima | 430 | 30 | 8/3/1992 |

Foreign Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Country | Class | Sub Class | Translation Yes/No |
|-------------|-----------|-----------------|------|---------|-------|-----------|--------------------|
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Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

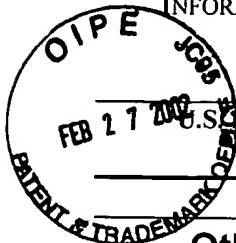
| Exam. Init. | Ref. Des. | Citation |
|-------------|-----------|--|
| 8F | C1 | Bishop <i>et al.</i> , "Use of Scatterometry for resist process control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:441-452, 1992. |
| 8F | C2 | Hickman <i>et al.</i> , "Use of diffracted light from latent images to improve lithography control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1464:245-257, 1991. |
| 8F | C3 | McNeil <i>et al.</i> , "Scatterometry applied to microelectronics processing – Part 1," <i>Solid State Technology</i> , 37(3):29-56, 1993. |
| 8F | C4 | Miller and Mellicamp, "Development of an end-point detection procedure for the post-exposure bake process," <i>Integrated circuit metrology, inspection, and process control IX</i> : 20-22, February, 1995, Santa Clara, California, <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2439:78-88, 1995. |
| 8F | C5 | Milner <i>et al.</i> , "Latent image exposure monitor using scatterometry," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:274-283, 1992. |
| 8F | C6 | Prins <i>et al.</i> , "Scatterometric sensor for PEB process control," <i>Metrology, inspection, and process control for microlithography</i> , X:11-13, March, 1996, Santa Clara, California, <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2725:710-719, 1996. |

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EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

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| Form PTO-1449 (modified) | | Atty. Docket No. 2000.070500/SFD | Serial No. 09/897,624 |
| List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | | Applicants Marilyn I. Wright | |
| FEB 21 2001 U.S. Patent Documents See Page 1 | | Filing Date: July 2, 2001 | Group: 2812 2823 |
| | | Other Art See Page 1-2 | |



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| gk | C8 | Raymond <i>et al.</i> , "Multiparameter process metrology using scatterometry," In: <i>Optical characterization techniques for high-performance microelectronic device manufacturing II, SPIE – The International Society for Optical Engineering</i> , 2638:84-93, Austin, Texas, October 25-26, 1995. |
| gk | C7 | Raymond <i>et al.</i> , "Scatterometric sensor for lithography," In: <i>Manufacturing process control for microelectronic devices and circuits, SPIE – The International Society for Optical Engineering</i> , 2336:37-49, Austin, Texas, October 20-21, 1994. |
| gk | C9 | Sturtevant <i>et al.</i> , "Post-exposure bake as a process-control parameter for chemically-amplified photoresist," <i>Metrology, inspection, and process control for microlithography, VII:2-4, March, 1993, Santa Jose, California, SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , vol. 1926, 1993. |
| gk | C10 | Sturtevant <i>et al.</i> , "Use of scatterometric latent image detector in closed loop feedback control of linewidth," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2196:352-359, 1994. |
| | | |

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| ✓ | A1 | 6,051,348 | 4/18/00 | Marinaro <i>et al.</i> | 430 | 30 | |
| ✓ | A2 | 6,245,584 B1 | 6/12/01 | Marinaro <i>et al.</i> | 438 | 14 | |
| | A3 | | | | | | |

Foreign Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Country | Class | Sub Class | Translation Yes/No |
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| | C1 | |
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